

Bhowmik 12-146-QSMOJO2
KOFFICE

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Application of:

Group Art Unit: 2826

Siddhartha Bhowmik, et al.

Examiner: Fazli Erdem

Serial No.: 09/967,094

Filed: September 28, 2001

Title: A BARRIER LAYER FOR INTERCONNECT

STRUCTURES OF A SEMICONDUCTOR WAFER AND METHOD FOR DEPOSITING

THE BARRIER LAYER

TECHNOLOGY CENTER 2800

Commissioner for Patents Box Non-Fee Amendment Washington, DC 20231

RESPONSE

The paper is submitted in response to the Office Action mailed on August

28, 2002, for which a response is due not later than November 28, 2002.

AMENDMENT

IN THE SPECIFICATION:

Please amend the specification as follows:

IN THE CLAIMS:

Please amend the claims as follows:

- 1. (Amended) [A] An interconnect structure, comprising:
 - (a) a substrate having disposed thereon a topographical

structure including a dielectric material and a recess formed therein;

12/04/2002 AOSHAN1 00000063 09967094

01 FC:1201

84.00 OP